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PATENT NUMBER and  
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM 10076129	FILING DATE 02/13/2002	CLASS 438	SUBCLASS J	GAU 415 1785	EXAMINER Gundean
<b>**APPLICANTS:</b> He Y.; Kwok Albert; Abe Tsukasa; Wu Han-Ming;					
<b>**CONTINUING DATA VERIFIED:</b>					
<b>** FOREIGN APPLICATIONS VERIFIED:</b>					
PG-PUB <input type="checkbox"/> DO NOT PUBLISH		RESCIND <input type="checkbox"/>			
Foreign priority claimed 35 USC 119 conditions met		<input type="checkbox"/> yes <input checked="" type="checkbox"/> no		ATTORNEY DOCKET NO	
Verified and Acknowledged Examiners's initials		<input type="checkbox"/> yes <input checked="" type="checkbox"/> no		10559-583001 / P12764	
TITLE : Plasma etching uniformity control					

U.S. DEPT. OF COMM /PAT. & TM-PTO-436L (Rev. 12-94)

<b>NOTICE OF ALLOWANCE MAILED</b>		<b>CLAIMS ALLOWED</b>	
		Total Claims	
		Print Claim for O.G.	
<b>ISSUE FEE</b>		<b>DRAWING</b>	
Amount Due	Date Paid	Sheets Drwg.	Fig. Drwg.
		Print Fig.	
<input type="checkbox"/> <b>TERMINAL DISCLAIMER</b>		Primary Examiner	
		PREPARED FOR ISSUE	
		Applicati n Examiner	
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